

Conference Chairs

Rafał Walczak – Chair of ELTE Conference
Karol Malecha – Chair of IMAPS Conference

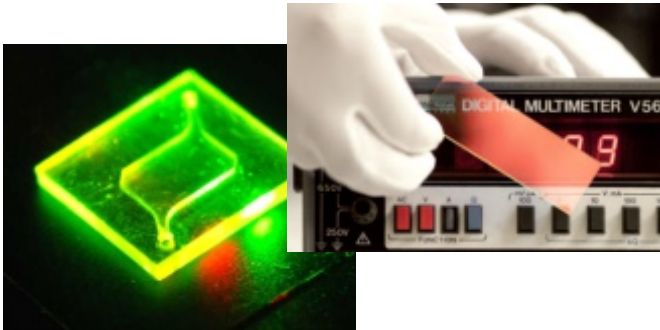
Organizing Committee

Jarosław Domaradzki - Chair
Jarosław Serafińczuk
Paweł Knapkiewicz
Wojciech Kubicki
Mateusz Czok
Laura Jasińska
Krzysztof Stojek
Jarosław Wojtowicz



Contact

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Important dates

May 10th – the deadline of abstract submission
May 24th – the notification of acceptance
June 21st – the deadline for the conference fee payment
June 21st – the deadline for the hotel booking by participants.

Conference fees (Early Bird, before 21th June)

1350 PLN – full participants
850 PLN – students and PhD students
450 PLN – accompanying persons

Costs of accommodation are not included in the conference fee

Conference place

The conference will be held at Wrocław University of Science and Technology, Conference Centre (building D-20), Janiszewskiego 8, 50-372 Wrocław

Organizer

Wrocław University of Science and Technology
Faculty of Microsystem Electronics and Photonics



Conference Centre (D-20)

Main building (A-1)



Wrocław University
of Science and Technology

13th CONFERENCE
“ELECTRON TECHNOLOGY”
ELTE 2019



AND

43rd INTERNATIONAL
MICROELECTRONICS AND PACKAGING
IMAPS POLAND CONFERENCE



Honorary Patronage of the Rector of
Wrocław University of Science and Technology
Prof. Cezary Madryas

4 - 6 September 2019

Wrocław University of Science and Technology



www.elteimaps2019.pwr.edu.pl

Conference topics - ELTE

1. Micro- and nanoelectronics
 - a) electrical, mechanical and thermal modelling/design of semiconductor structures and devices, integrated circuits and systems
 - b) simulation of technological processes
 - c) micro- and nanotechnologies (also with application of electron, ion and molecular beams)
 - d) spintronics and magnetoelectronics
 - e) characterization and diagnostics of technological processes, semiconductor structures, devices and integrated circuits
2. Photonics
 - a) semiconductor light sources
 - b) detectors and photovoltaic cells
 - c) novel materials for optoelectronics
 - d) passive optoelectronic devices
 - e) materials with nonlinear optical properties - physics, technology, applications
3. Microsystems
 - a) electrical, mechanical and thermal modelling/design of microsystems
 - b) fabrication and characterization of MEMS and MOEMS structures
 - c) sensors and smart sensor structures
 - d) lab-on-a-chip systems
 - e) micro- and nanobiosystems
 - f) microsystems for IoT and Industry 4.0

4. Electronic materials
 - a) fabrication and comprehensive characterization of electronic materials
 - b) nanotechnologies in fabrication of electronic and photonic materials
 - c) nano- and biomaterials in electronic and photonic structures/devices and microsystems
 - d) advanced analysis methods for electronic materials and structures



One of the Wrocław dwarfs.

Conference topics - IMAPS

- Hybrid and Semiconductor Technology
- Design Methods and Computer Simulations
- Electronics Materials and Components
- Microcircuits Applications
- Thick-Film and Thin-Film Sensors
- Packaging and PCB
- Quality and Reliability Evaluation
- Thermal Management
- Optoelectronics and Photovoltaics



University cable car - 'Polinka'

Boulevard of Wrocław
University of Science
and Technology



General information

- Presentations/posters for ELTE can be prepared either in English or in Polish
- Presentations/posters for IMAPS should be prepared in English
- Abstracts and full texts of papers should be prepared in English
- The conference presentations will be divided into plenary sessions, section sessions and poster sessions
- Students, PhD students and young researchers (below 32 years old) can participate in contests for best papers in particular thematic sections
- Exhibition of technological and diagnostic equipment is planned during the conference
- Papers chosen by Scientific Committees will be recommended for publishing in international technical journals